Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	530	((bump\$1 or defect\$1 or mask\$1) with (repair\$3 or remov\$3) with quartz)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 16:19
S2	69	((bump\$1 or defect\$1 or mask\$1) with (repair\$3 or remov\$3) with quartz)	EPO; JPO	OR	OFF	2005/09/28 14:16
<b>S3</b>	392	((bump\$1 or defect\$1 or mask\$1) with (repair\$3 or remov\$3) with quartz)	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:16
S4	543	((bump\$1 or defect\$1 or mask\$1) and (repair\$3 or remov\$3) and quartz).clm.	US-PGPUB; USPAT	OR .	OFF	2005/09/29 12:54
S5	849	S4 or S1	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:17
S6	497	S5 and ion	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:18
S7	29	S5 and (nanomachining or afm)	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:19
S8	8764	(ludwig or verbeek).in.	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:23
S10	46	(bump\$1 or defect\$1 or mask\$1) and (quartz or silica) and S8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	.OR	OFF	2005/09/28 14:24
S11	102	((ludwig and ralf) or (verbeek and martin)).in.	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:48
S12	42	(bump\$1 or defect\$1 or mask\$1 or quartz) and S11	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:24
S13	593	((bump\$1 or defect\$1 or mask\$1 or photomask\$1) with (repair\$3 or remov\$3) with quartz)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:25
S14	499	((bump\$1 or defect\$1 or mask\$1 or photomask\$1) near20 (repair\$3 or remov\$3) near20 quartz)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:26

S15	15966	((bump\$1 or defect\$1 or mask\$1 or photomask\$1) near20 (repair\$3 or remov\$3) near20 (quartz or silic\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:26
S16	4028	(bump\$1 or defect\$1) near20 (repair\$3 or remov\$3) near20 (quartz or silic\$4 or photomask\$1 or mask\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:29
S17	406	(216/12).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:29
S18	271	216/12	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:29
S19	77	(bump\$1 or defect\$1) and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:44
S20	6115	430/5	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:29
S21	7599	(430/5).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:30
S22	103	(quartz or silica) and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:30
S23	39	(bump\$1 or defect\$1) and (quartz or silica) and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:31
S24	1024	(bump\$1 or defect\$1) and (quartz or silica) and (S18 or S20)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:32

S25	706	(bump\$1 or defect\$1) and (quartz or silica) and (\$18 or \$20) and (ion or afm or machine\$3 or nanomachin\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:33
S26	706	(bump\$1 or defect\$1) and (quartz or silica) and (S18 or S20) and (ion or afm or machine\$3 or nanomachin\$3)	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:33
S27	157	(bump\$1 or defect\$1).clm. and (quartz or silica) and (S18 or S20) and (ion or afm or machine\$3 or nanomachin\$3)	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:36
S28	141	(bump\$1 or defect\$1).clm. and (quartz or silica) and (\$18 or \$20) and ion	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:36
S29	84	(bump\$1 or defect\$1).clm. and (quartz or silica) and (S18 or S20) and (afm or machine\$3 or nanomachin\$3)	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:36
S30	68	(bump\$1 or defect\$1) clm. and (quartz or silica) and (\$18 or \$20) and (afm or machine\$3 or nanomachin\$3) and ion	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:44
S31	933	(216/52).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:43
S32	450	216/52	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:43
S33	128	(bump\$1 or defect\$1) and S32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:44
S34	129	(bump\$1 or defect\$1 or divot\$1) and S32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/28 14:44
S35	68	(bump\$1 or defect\$1 or divot\$1). clm. and (quartz or silica) and (S18 or S20) and (afm or machine\$3 or nanomachin\$3) and ion	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:11

S36	42	(bump\$1 or defect\$1 or divot\$1) and (quartz or silica) and (ion or FIB)	JPO	OR	OFF	2005/09/28 14:46
S37	35	(bump\$1 or defect\$1 or divot\$1) and (nanomachin\$3 or machin\$3 or afm or micromachin\$3) and (ion or FIB)	JPO	OR	OFF	2005/09/28 14:50
S38	10	(bump\$1 or defect\$1 or divot\$1) and (afm or (force adj microscop\$1)) and (ion or FIB)	JPO	OR	OFF	2005/09/28 14:51
S39	24	((bump\$1 or defect\$1 or divot\$1) and (afm or (force adj microscop\$1)) and (ion or FIB)). clm.	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:52
S40	26	((bump\$1 or defect\$1 or divot\$1) with (afm or (force adj microscop\$1)) with (ion or FIB))	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:52
S41	73	((bump\$1 or defect\$1 or divot\$1) same (afm or (force ad) microscop\$1)) same (ion or FIB))	US-PGPUB; USPAT	OR	OFF	2005/09/28 14:59
S42	2	("6322935").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR ·	OFF	2005/09/28 15:00
S43	103	((bump\$1 or defect\$1 ) and (repair\$3 or remov\$3) and quartz).clm.	US-PGPUB; USPAT	OR	OFF	2005/09/29:12:54
S44	2	(bump\$1 or defect\$1 ) near10 (repair\$3 or remov\$3) near10 (nanomachin\$3)	US-PGPUB; USPAT	OR	OFF	2005/09/29 12:56
S45	3	(bump\$1 or defect\$1 ) same (repair\$3 or remov\$3) same (nanomachin\$3)	US-PGPUB; USPAT	OR	OFF	2005/09/29 12:55
S46	12	(bump\$1 or defect\$1 ) near10 (repair\$3 or remov\$3) near10 (AFM)	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:01
S48	1	(bump\$1 or defect\$1 ) near15 (repair\$3 or remov\$3) near15 (diamond adj tip)	US-PGPUB; USPAT	OR	OFF	2005/09/29 12:58
S49	65	(bump\$1 or defect\$1 ) near15 (repair\$3 or remov\$3) near15 diamond	US-PGPUB; USPAT	OR	OFF	2005/09/29 12:58
S50	9	(bump\$1 or defect\$1 ) and nanomachin\$3.ti.	US-PGPUB; USPAT	OR	OFF	2005/09/29 12:59
S52	9	(bump\$1 or defect\$1) and nanomachin\$3.ti.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:00
S53	6	(AFM) and nanomachin\$3.ti.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:00

S54	12	(bump\$1 or defect\$1 ) near10 (repair\$3 or remov\$3) near20 (AFM)	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:05
S55	25	(quartz or mask\$1) near10 (repair\$3 or remov\$3) near20 (AFM)	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:05
S56	205	((bump\$1 or defect\$1 or mask\$3 or photomask\$1) and (quartz or silica or glass) and (machining or nanomachin\$3 or nano-machin\$3 or afm or (force adj microscop\$1) or grind\$3)).clm.	US-PGPUB; USPAT	OR .	OFF	2005/09/29 13:15
S57	87	((bump\$1 or defect\$1 or mask\$3 or photomask\$1) and (quartz or silica or glass) and (machining or nanomachin\$3 or nano-machin\$3)).clm.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:18
S58	7343	(bump\$1 or defect\$1) and (mask\$3 or photomask\$1) and repair\$3	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:19
S59	89	((bump\$1 or defect\$1) and (mask\$3 or photomask\$1) and repair\$3)	JPO	OR	OFF	2005/09/29 13:20
S60	156	((bump\$1 or defect\$1) and (mask\$3 or photomask\$1) and repair\$3).ab.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:19
S61	40	((bump\$1 or defect\$1) and (mask\$3 or photomask\$1) and repair\$3).ti.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:44
S64	226	((bump\$1 or defect\$1) and (mask\$3 or photomask\$1) and repair\$3).clm.	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:19
S66	268	(S60 or S61 or S64)	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:45
S67	26	(S60 or S61 or S64) and AFM	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:57
S68	2	(S60 or S61 or S64) and nanomachin\$3	US-PGPUB; USPAT	OR	OFF	2005/09/29 13:57
S69	6	(bump\$1 or defect\$1 or mask\$1 or photomask\$1) and (takaoka and osamu and yabe and satoru). in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 16:21
S70	.53	(bump\$1 or defect\$1 or mask\$1 or photomask\$1) and ((takaoka and osamu) (yabe and satoru)).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 16:21

S71	44	(bump\$1 or defect\$1 or mask\$1 or photomask\$1) and ((takaoka near2 osamu) (yabe near2 satoru)).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 17:31
S73	10	(bump\$1 or defect\$1 or mask\$1 or photomask\$1) and ((martin near2 verbeek) (ludwig near2 ralf)).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29:17:34
S74	5	(bump\$1 or defect\$1 or mask\$1 or photomask\$1) and ((roy near2 white) (marty near2 klos) (ron near2 bozak)).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/29 17:36